

REMARKS

Claims 1-4, 6, 13-15, 17, 18, 21-28, 31, 32, 36 and 37 are pending, with claims 1-4, 17 and 18 being independent. Claims 1 and 2 have been amended and claims 5, 12, 19, 20, 29 and 30 have been canceled. Support for the amendment may be found in the application at, for example, page 21, line 24 to page 22, line 2. No new matter has been introduced.

Claims 1-6, 12-15, 17-22, 36 and 37 have been provisionally rejected for obviousness-type double patenting over claims 1-22 of co-pending Application No. 10/662,357 in view of Pichler (U.S. Patent Publication No. 2004/0187917) or Song (U.S. Patent No. 6,872,473). Applicant requests that this rejection be held in abeyance until the claims of this application and those of the '357 application are otherwise found to be allowable.

Claims 1-6, 12-15, 17-32, 36 and 37 have been rejected as being unpatentable over Kawase (U.S. Patent Publication No. 2003/0001992) in view of Pichler or Song.

With respect to claims 1 and 2, and their dependent claims, applicant requests reconsideration and withdrawal of this rejection in view of the amendments to claims 1 and 2, which have been amended to recite "a mixed film containing fluoroplastics and metallic oxide formed over the second electrode," as shown in the application at, for example, page 21, line 24 to page 22, line 2. By forming a mixed film containing fluoroplastics and metallic oxide, fluoroplastics content in the mixed film can be controlled, and another film can be stacked on the mixed film. Accordingly, applicant requests reconsideration and withdrawal of the rejection because neither Kawase, Pichler, Song nor any combination of the three describes or suggests such a mixed film.

With respect to claims 3, 4, 17 and 18, and their dependent claims, applicant requests reconsideration and withdrawal of the rejection because neither Kawase, Pichler, Song nor any combination of the three describes or suggests an insulating film over a thin film transistor and including a first insulating film and a second insulating film formed on the first insulating film, where the first insulating film comprises a material selected from the group consisting of acrylic, polyamide, and polyimide, and the second insulating film is a mixed film comprising

fluoroplastics and metallic oxide, as recited in claims 3 and 17, or an insulating film over the thin film transistor and comprising fluoroplastics and metallic oxide, as recited in claims 4 and 18.

While the rejection indicates that the interface between the film 400 of Song, which contains fluoroplastics, and the film 500 of Song, which may include metallic oxide, would include mixed fluoroplastics and metallic oxide, this interface is not a film. Moreover, with respect to claims 3 and 17, even if this interface were said to be a film, it could not be said to be a second insulating film "formed on" a first insulating film that comprises a material selected from the group consisting of acrylic, polyamide, and polyimide, since the interface is formed on the film 400, which does not contain those materials. Accordingly, the rejection should be withdrawn.

Applicant submits that all claims are in condition for allowance.

The fee in the amount of \$910 in payment of the request for continued examination fee (\$790) and the one-month extension fee (\$120) is being paid concurrently herewith on the Electronic Filing System (EFS) by way of Deposit Account authorization. Please apply any other charges or credits to Deposit Account No. 06-1050.

Respectfully submitted,

Date: _____

7/31/06



John F. Hayden
Reg. No. 37,640

Fish & Richardson P.C.
1425 K Street, N.W.
11th Floor
Washington, DC 20005-3500
Telephone: (202) 783-5070
Facsimile: (202) 783-2331